

DERWENT-ACC-NO: 1992-232593

DERWENT-WEEK: 199817

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TITLE: Compsn. for removing asphaltene-resin-paraffin deposits  
- contains inhibitor of salt deposits, nonionic  
surfactant, hydrochloric acid and water

INVENTOR: LONINA, T P; PIGOROVA, V A; RAGULIN, V A

PATENT-ASSIGNEE: BASHKIR OIL IND RES DES INST[BASHR]

PRIORITY-DATA: 1989SU-4703984 (June 12, 1989)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
SU 1682374 A1	October 7, 1991	N/A	006	C09K 003/00

APPLICATION-DATA:

PUB-NO	APPL-DESCRIPTOR	APPL-NO	APPL-DATE
SU 1682374A1	N/A	1989SU-4703984	June 12, 1989

INT-CL (IPC): C09K003/00

ABSTRACTED-PUB-NO: SU 1682374A

BASIC-ABSTRACT:

The compsn. contains (in wt.%): inhibitor of salt deposits (I) 2.0-8.0, nonionic surfactant 0.3-0.4, hydrochloric acid 17.5-19.0 and balance water.

Hydroxyethylated alkyl phenols, based on alpha-olefins and propylene trimers, are used as nonionic surfactants. (I) contains (in wt.%): nitrilo-trimethyl phosphonic acid 28-32, methylimino- dimethyl phosphonic acid 3-15, phosphorous acid 1-5, urea 15-18, ethylene glycol 7-9, ammonia 10-13 and balance water.

USE/ADVANTAGE - In oil industry, as a compsn. for removing complex deposits including asphaltene-resin-paraffins, iron sulphide and calcium carbonate from oil extn., transporting and storage equipment. Increased efficiency is obtd. Bul.37/7.10.91

CHOSEN-DRAWING: Dwg.0/0

TITLE-TERMS: COMPOSITION REMOVE ASPHALTENE RESIN PARAFFIN DEPOSIT  
CONTAIN

INHIBIT SALT DEPOSIT NONIONIC SURFACTANT HYDROCHLORIC ACID WATER

DERWENT-CLASS: A97 E19 G04 H03

CPI-CODES: A12-W12B; E05-G03C; E10-A13B; E10-E04M1; E11-Q02; E31-B03D;  
E31-K07; E32-A02; E34-D03; E35-U05; G04-B08; H01-C10; H03-X;

CHEMICAL-CODES:

Chemical Indexing M3 \*01\*

Fragmentation Code

G011 G012 G013 G100 H4 H401 H481 H5 H541 H581  
H582 H583 H584 H589 H721 H8 M220 M221 M222 M223  
M224 M225 M226 M231 M232 M233 M240 M281 M312 M321  
M322 M323 M332 M342 M383 M391 M392 M393 M414 M510  
M520 M531 M540 M782 M903 M904 Q337 Q412 Q607 Q616  
R023

Markush Compounds

199228-E8001-M

Chemical Indexing M3 \*02\*

Fragmentation Code

B415 B702 B713 B720 B742 B743 B815 B832 B833 H1  
H103 H181 M210 M211 M273 M280 M281 M311 M322 M323  
M342 M361 M392 M393 M411 M510 M520 M530 M540 M620  
M782 M903 M904 Q337 Q412 Q607 R023

Markush Compounds

199228-E8002-M

Chemical Indexing M3 \*03\*

Fragmentation Code

B115 B713 B720 B813 B831 C101 C108 C800 C802 C804  
C805 C807 M411 M782 M903 M904 M910 Q337 Q412 Q607  
R023

Specific Compounds

01970M

Chemical Indexing M3 \*04\*

Fragmentation Code

K0 L4 L432 M280 M320 M416 M620 M782 M903 M904  
M910 Q337 Q412 Q607 R023

Specific Compounds

00123M

Chemical Indexing M3 \*05\*

Fragmentation Code

H4 H402 H482 H8 M280 M312 M321 M332 M342 M383  
M391 M416 M620 M782 M903 M904 M910 Q337 Q412 Q607  
R023

Specific Compounds

00822M

Chemical Indexing M3 \*06\*

Fragmentation Code

C500 C730 C800 C801 C802 C804 C806 C807 M411 M782  
M903 M904 M910 Q337 Q412 Q607 R023

Specific Compounds

01713M

Chemical Indexing M3 \*07\*

Fragmentation Code

C017 C100 C101 C730 C800 C801 C804 C805 C806 C807

M411 M782 M903 M904 M910 Q337 Q412 Q607 R023

Specific Compounds

01704M

UNLINKED-DERWENT-REGISTRY-NUMBERS: 0123U; 0822U; 1704U; 1713U; 1970U

POLYMER-MULTIPUNCH-CODES-AND-KEY-SERIALS:

Key Serials: 0226 0236 0252 1983 2002 2008 2546 2585 3273 3304

Multipunch Codes: 014 02& 039 041 046 050 231 240 244 251 478 51& 575 583 589

59& 623 624 646 722

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: C1992-105248